Beams & Plasmas
Laboratory of vacuum technologies plus, LLC

Ion sputtering unit NIKA-153

Vacuum deposition unit Nika-2013-500 is designed for double-sided deposition of transparent conductive coatings (In2O3: SnO2) on layers of organic and organometallic semiconductors with control of the thickness of the resulting film by the resistance witness. The installation has automatic software control, ensuring the implementation of the technological process in the following modes:

- adjustment mode - control of mechanisms and devices for performing adjustment, repair and maintenance work;
- manual mode - control of installation elements in compliance with all interlocks, excluding the occurrence of emergency situations;
- automatic mode - implementation of an automatic cycle
- technological program (technological recipe)

The vacuum chamber of the installation is equipped with:

- ion source IBS-250;
- water-cooled table;
- water-cooled target holder.

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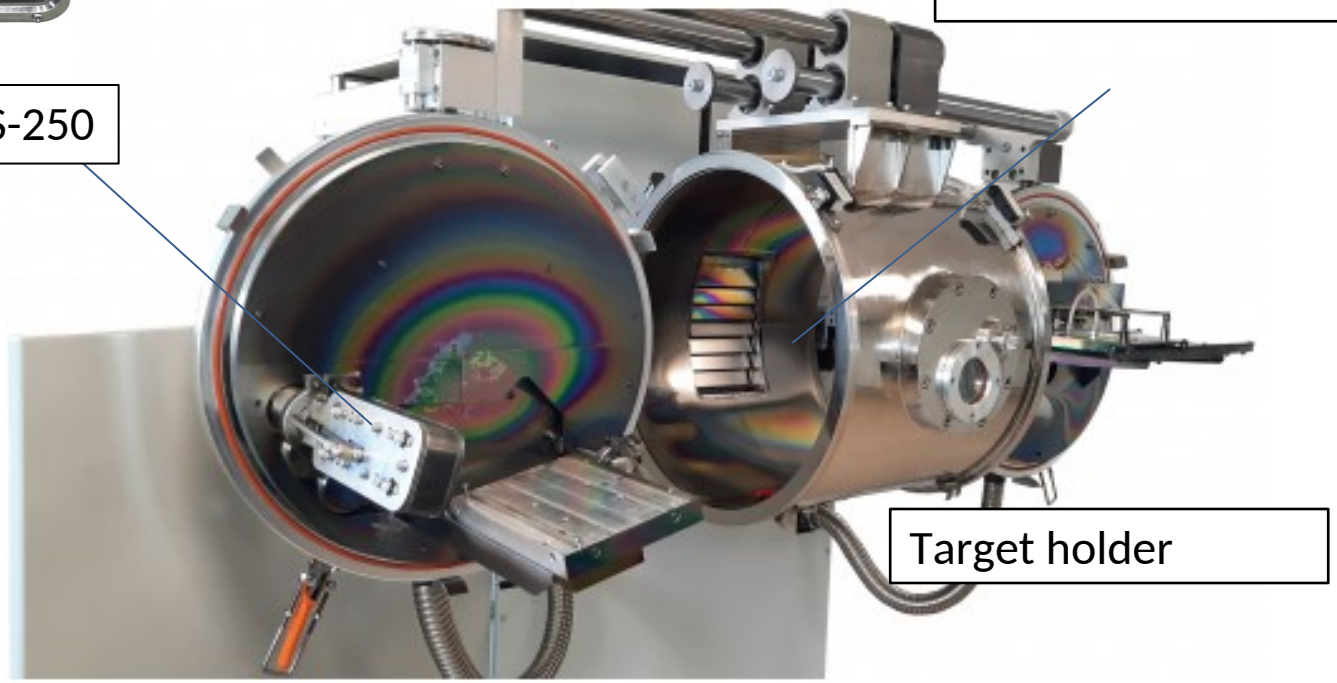
Layout and characteristics

Ion beam source IBS-250



The vacuum chamber of the installation is equipped with:
water-cooled table;
water cooled target holder;
ion beam source IBS-250

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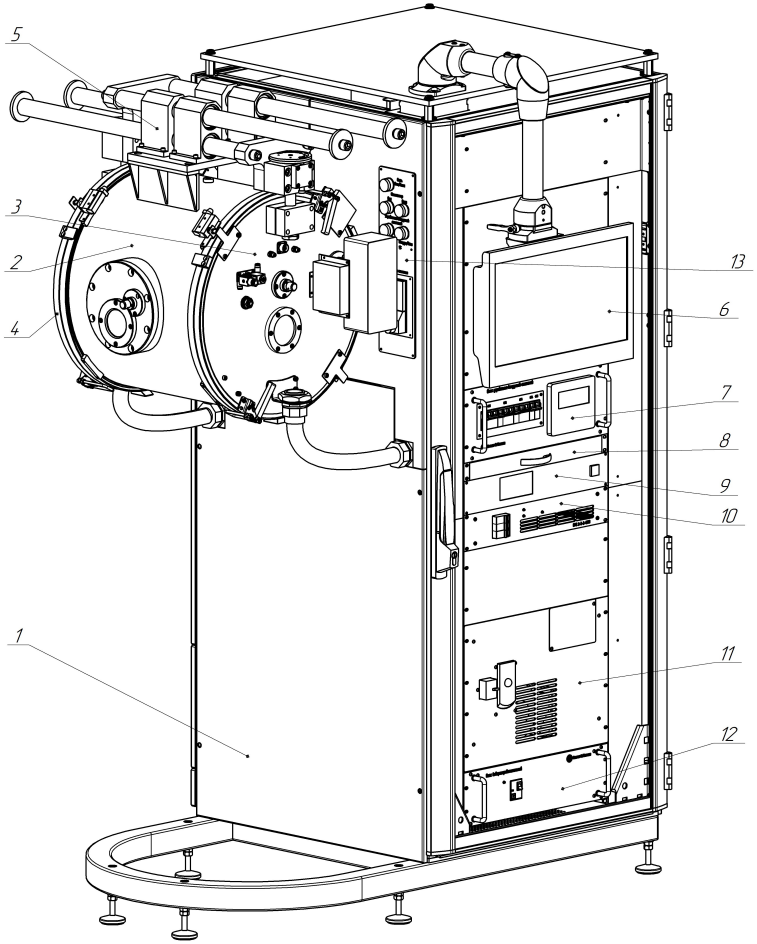
Components



1 - frame;
2 - vacuum chamber;
3 - front flange;
4 - rear flange;
5 - suspension;
6 - monitor;
7 - vacuum system control unit;
8 - shelf with keyboard and mouse;
9 - turbomolecular pump controller;
10 - power supply unit of the ion source;
11 - SOVA;
12 - water distribution unit;
13 - control panel.

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Layout